

Jiro Matsuo

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272
papers

4,650
citations

36
h-index

55
g-index

307
ext. papers

4,929
ext. citations

2.4
avg, IF

5.12
L-index

#	Paper	IF	Citations
272	Materials processing by gas cluster ion beams. <i>Materials Science and Engineering Reports</i> , 2001 , 34, 231-295	3.9	359
271	Precise and fast secondary ion mass spectrometry depth profiling of polymer materials with large Ar cluster ion beams. <i>Rapid Communications in Mass Spectrometry</i> , 2009 , 23, 1601-6	2.2	174
270	Organic depth profiling of a nanostructured delta layer reference material using large argon cluster ions. <i>Analytical Chemistry</i> , 2010 , 82, 98-105	7.8	141
269	Measurements of secondary ions emitted from organic compounds bombarded with large gas cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 256, 493-496	1.2	140
268	Molecular depth profiling of multilayer structures of organic semiconductor materials by secondary ion mass spectrometry with large argon cluster ion beams. <i>Rapid Communications in Mass Spectrometry</i> , 2009 , 23, 3264-8	2.2	86
267	Incident angle dependence of the sputtering effect of Ar-cluster-ion bombardment. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 489-492	1.2	76
266	Molecular dynamics simulation of damage formation by cluster ion impact. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 49-52	1.2	73
265	Nano-processing with gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2000 , 164-165, 944-959	1.2	73
264	Surface treatment of diamond films with Ar and O ₂ cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1999 , 148, 639-644	1.2	69
263	Generation of the large current cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 902-906	1.2	67
262	Non-linear processes in the gas cluster ion beam modification of solid surfaces. <i>Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing</i> , 1998 , 253, 249-257	5.3	59
261	Characterization of structural dynamics of VO ₂ thin film on c-Al ₂ O ₃ using in-air time-resolved x-ray diffraction. <i>Physical Review B</i> , 2010 , 82,	3.3	58
260	STM observation of HOPG surfaces irradiated with Ar cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 498-502	1.2	58
259	A new secondary ion mass spectrometry (SIMS) system with high-intensity cluster ion source. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2004 , 219-220, 463-467	1.2	55
258	Reactive sputtering by SF ₆ cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 484-488	1.2	54
257	A fragment-free ionization technique for organic mass spectrometry with large Ar cluster ions. <i>Applied Surface Science</i> , 2008 , 255, 1588-1590	6.7	54
256	Surface processing by gas cluster ion beams at the atomic (molecular) level. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1996 , 14, 781-785	2.9	54

255	Cluster size dependence of sputtering yield by cluster ion beam irradiation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2006 , 242, 179-181	1.2	52
254	High sputtering yields of organic compounds by large gas cluster ions. <i>Applied Surface Science</i> , 2008 , 255, 1148-1150	6.7	51
253	Smoothing of YBa ₂ Cu ₃ O ₇ films by ion cluster beam bombardment. <i>Applied Physics Letters</i> , 1998 , 72, 246-248	3.4	51
252	Molecular dynamics study of damage formation characteristics by large cluster ion impacts. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 202, 278-282	1.2	49
251	Peptide Fragmentation and Surface Structural Analysis by Means of ToF-SIMS Using Large Cluster Ion Sources. <i>Analytical Chemistry</i> , 2016 , 88, 3592-7	7.8	46
250	Proposal for a hardness measurement technique without indenter by gas-cluster-beam bombardment. <i>Physical Review B</i> , 2000 , 61, 8744-8752	3.3	45
249	Surface modifications by gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1995 , 106, 165-169	1.2	45
248	Matrix-free high-resolution imaging mass spectrometry with high-energy ion projectiles. <i>Journal of Mass Spectrometry</i> , 2009 , 44, 128-36	2.2	44
247	Cluster ion beam process technology. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 820-829	1.2	43
246	Atomic level smoothing of CVD diamond films by gas cluster ion beam etching. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1996 , 112, 248-251	1.2	43
245	Angular distributions of the particles sputtered with Ar cluster ions. <i>Materials Chemistry and Physics</i> , 1998 , 54, 262-265	4.4	42
244	Surface smoothing mechanism of gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2000 , 161-163, 980-985	1.2	42
243	Strongly reduced fragmentation and soft emission processes in sputtered ion formation from amino acid films under large Ar(n) ⁺ (n ≥ 200) cluster ion bombardment. <i>Rapid Communications in Mass Spectrometry</i> , 2012 , 26, 1-8	2.2	41
242	What size of cluster is most appropriate for SIMS?. <i>Applied Surface Science</i> , 2008 , 255, 1235-1238	6.7	41
241	Sputtering of elemental metals by Ar cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 459-463	1.2	40
240	Progress and applications of cluster ion beam technology. <i>Current Opinion in Solid State and Materials Science</i> , 2015 , 19, 12-18	12	38
239	Low-damage surface processing by gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1995 , 99, 229-232	1.2	38
238	Secondary ion mass spectrometry with gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2002 , 190, 860-864	1.2	37

237	Hard DLC film formation by gas cluster ion beam assisted deposition. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 201, 405-412	1.2	36
236	Molecular dynamics simulations for gas cluster ion beam processes. <i>Vacuum</i> , 2010 , 84, 994-998	3.7	35
235	Cluster size dependence of the impact process on a carbon substrate. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1999 , 153, 264-269	1.2	35
234	Shallow junction formation by polyatomic cluster ion implantation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 345-348	1.2	34
233	Cold ablation driven by localized forces in alkali halides. <i>Nature Communications</i> , 2014 , 5, 3863	17.4	33
232	Reduction of boron transient enhanced diffusion in silicon by low-energy cluster ion implantation. <i>Materials Chemistry and Physics</i> , 1998 , 54, 80-83	4.4	33
231	Novel SIMS system with focused massive cluster ion source for mass imaging spectrometry with high lateral resolution. <i>Applied Physics Express</i> , 2014 , 7, 056602	2.4	32
230	Analysis of organic semiconductor multilayers with Ar cluster secondary ion mass spectrometry. <i>Surface and Interface Analysis</i> , 2011 , 43, 95-98	1.5	32
229	Study on Chlorine Adsorbed Silicon Surface Using Soft-X-Ray Photoemission Spectroscopy. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, 2025-2029	1.4	32
228	SIMS with highly excited primary beams for molecular depth profiling and imaging of organic and biological materials. <i>Surface and Interface Analysis</i> , 2010 , 42, 1612-1615	1.5	31
227	Surface smoothing effects with reactive cluster ion beams. <i>Materials Chemistry and Physics</i> , 1998 , 54, 106-110	4.4	31
226	Cluster ion bombardment on atomically flat Au(111) solid surfaces. <i>Materials Chemistry and Physics</i> , 1998 , 54, 76-79	4.4	30
225	Secondary ion mass spectrometry with gas cluster ion beams. <i>Applied Surface Science</i> , 2003 , 203-204, 214-218	6.7	30
224	Surface modification with gas cluster ion beams from fundamental characteristics to applications. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2004 , 216, 379-389	1.2	29
223	Hot electron injection driven phase transitions. <i>Physical Review B</i> , 2012 , 86,	3.3	27
222	Molecular dynamics simulations of surface modification and damage formation by gas cluster ion impacts. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2006 , 242, 517-519	1.2	27
221	Photo-induced lattice softening of excited-state VO ₂ . <i>Applied Physics Letters</i> , 2011 , 99, 051903	3.4	26
220	Comparison of MeV monomer ion and keV cluster ToF-SIMS. <i>Surface and Interface Analysis</i> , 2011 , 43, 249-252	1.5	26

219	Cluster ion beam processing. <i>Materials Science in Semiconductor Processing</i> , 1998 , 1, 27-41	4.3	26
218	Study of Ar cluster ion bombardment of a sapphire surface. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 493-497	1.2	25
217	Energy dependence of a single trace created by C60 ion impact. <i>Materials Chemistry and Physics</i> , 1998 , 54, 143-146	4.4	25
216	The effect of incident cluster ion energy and size on secondary ion yields emitted from Si. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 256, 528-531	1.2	25
215	Molecular dynamics and Monte-Carlo simulation of sputtering and mixing by ion irradiation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2001 , 180, 312-316	1.2	24
214	Gas cluster ion beam equipments for industrial applications. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1995 , 99, 244-247	1.2	24
213	A high performance 50 nm PMOSFET using decaborane (B/sub 10/H/sub 14/) ion implantation and 2-step activation annealing process		23
212	O2 cluster ion-assisted deposition for tin-doped indium oxide films. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2000 , 161-163, 952-957	1.2	23
211	Lateral Sputtering by Gas Cluster Ion Beams and its Applications to Atomic Level Surface Modification. <i>Materials Research Society Symposia Proceedings</i> , 1995 , 396, 149		23
210	Development of a TOF SIMS setup at the Zagreb heavy ion microbeam facility. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2014 , 332, 234-237	1.2	22
209	Selective Reduction Mechanism of Graphene Oxide Driven by the Photon Mode the Thermal Mode. <i>ACS Nano</i> , 2019 , 13, 10103-10112	16.7	21
208	Molecular dynamics simulation of a carbon cluster ion impacting on a carbon surface. <i>Materials Chemistry and Physics</i> , 1998 , 54, 139-142	4.4	21
207	Size effect in cluster collision on solid surfaces. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 257, 627-631	1.2	21
206	Transient enhanced diffusion from decaborane molecular ion implantation. <i>Applied Physics Letters</i> , 1998 , 73, 2015-2017	3.4	21
205	Effects on CO Oxidation Activity of Nano-Scale Au Islands and TiO2 Support Prepared by the Ionized Cluster Beam Method. <i>Japanese Journal of Applied Physics</i> , 1997 , 36, 813-818	1.4	20
204	Preparation and catalytic activity of nano-scale Au islands supported on TiO2. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 503-506	1.2	20
203	Indium oxide film formation by O2 cluster ion-assisted deposition. <i>Materials Chemistry and Physics</i> , 1998 , 54, 258-261	4.4	20
202	Molecular dynamics simulations of sequential cluster ion impacts. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2005 , 228, 46-50	1.2	20

201	Nanofabrication technology by gas cluster ion beams. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1996 , 14, 3951		20
200	Gas Cluster Ion Beam Processing for ULSI Fabrication. <i>Materials Research Society Symposia Proceedings</i> , 1996 , 427, 265		20
199	Sputtered ion emission under size-selected Ar ⁿ⁺ cluster ion bombardment. <i>Surface and Interface Analysis</i> , 2013 , 45, 138-142	1.5	19
198	Femtosecond electron diffraction: Preparation and characterization of (110)-oriented bismuth films. <i>Journal of Applied Physics</i> , 2012 , 111, 043504	2.5	19
197	The effect of incident energy on molecular depth profiling of polymers with large Ar cluster ion beams. <i>Surface and Interface Analysis</i> , 2011 , 43, 221-224	1.5	19
196	Sidewall polishing with a gas cluster ion beam for photonic device applications. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2005 , 241, 622-625	1.2	19
195	Chlorine molecular beam scattering study on Si(100)2 × 1: desorption products. <i>Applied Surface Science</i> , 1992 , 60-61, 126-130	6.7	19
194	Highly sensitive molecular detection with swift heavy ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011 , 269, 2251-2253	1.2	18
193	Low-Temperature Oxidation of Silicon by O ₂ Cluster Ion Beams. <i>Japanese Journal of Applied Physics</i> , 1996 , 35, 1450-1453	1.4	18
192	Yield enhancement of molecular ions with MeV ion-induced electronic excitation. <i>Applied Surface Science</i> , 2008 , 255, 1591-1594	6.7	18
191	Surface smoothing with large current cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2004 , 216, 191-195	1.2	18
190	High quality ITO film formation by the simultaneous use of cluster ion beam and laser irradiation. <i>Materials Chemistry and Physics</i> , 2002 , 74, 104-108	4.4	18
189	MeV-energy probe SIMS imaging of major components in animal cells etched using large gas cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2010 , 268, 1736-1740	1.2	17
188	Low damage smoothing of magnetic material films using a gas cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 257, 677-682	1.2	17
187	Sputtering effect of gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1995 , 99, 237-239	1.2	17
186	Peptide dissociation patterns in secondary ion mass spectrometry under large argon cluster ion bombardment. <i>Rapid Communications in Mass Spectrometry</i> , 2013 , 27, 1490-6	2.2	16
185	Surface morphology of PMMA surfaces bombarded with size-selected gas cluster ion beams. <i>Surface and Interface Analysis</i> , 2011 , 43, 120-122	1.5	16
184	Molecular dynamics study of glancing angle gas cluster irradiation on irregular-structured surfaces. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 261, 639-642	1.2	16

183	Surface structure dependence of impact processes of gas cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2004 , 216, 185-190	1.2	16
182	Decaborane (B/sub 10/H/sub 14/) ion implantation technology for sub-0.1- μm PMOSFETs. <i>IEEE Transactions on Electron Devices</i> , 1999 , 46, 683-689	2.9	16
181	Effects of bombardment by high energy gas cluster ion beams. <i>Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing</i> , 1996 , 217-218, 74-77	5.3	16
180	Reaction kinetics of chlorine on Si(111)7 \times 7 surfaces. <i>Surface Science</i> , 1993 , 283, 52-57	1.8	16
179	Development of gas cluster ion beam irradiation system with an orthogonal acceleration TOF instrument. <i>Surface and Interface Analysis</i> , 2013 , 45, 522-524	1.5	15
178	Modification of polycarbonate and polypropylene surfaces by argon ion cluster beams. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2001 , 19, 2050		15
177	SiO ₂ film formation at room temperature by gas cluster ion beam oxidation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1996 , 112, 83-85	1.2	15
176	Molecular dynamics simulations of surface smoothing and sputtering process with glancing-angle gas cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 257, 645-648	1.2	14
175	Polishing of Sidewall Surfaces Using a Gas Cluster Ion Beam. <i>Japanese Journal of Applied Physics</i> , 2004 , 43, L1253-L1255	1.4	14
174	STM observation of surface vacancies created by ion impact. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2000 , 164-165, 650-655	1.2	14
173	Effects of ambient pressure on Cu K α -ray radiation with millijoule and high-repetition-rate femtosecond laser. <i>Applied Physics B: Lasers and Optics</i> , 2010 , 99, 173-179	1.9	13
172	Defect characteristics by boron cluster ion implantation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 855-860	1.2	13
171	Etching, smoothing, and deposition with gas-cluster ion beam technology. <i>Surface and Coatings Technology</i> , 2000 , 133-134, 273-282	4.4	13
170	Chemical States of Bromine Atoms on SiO ₂ Surface after HBr Reactive Ion Etching: Analysis of Thin Oxide. <i>Japanese Journal of Applied Physics</i> , 1993 , 32, 3063-3067	1.4	13
169	Study on the detection limits of a new argon gas cluster ion beam secondary ion mass spectrometry apparatus using lipid compound samples. <i>Rapid Communications in Mass Spectrometry</i> , 2014 , 28, 917-20	2.2	12
168	Evaluation of Damage Layer in an Organic Film with Irradiation of Energetic Ion Beams. <i>Japanese Journal of Applied Physics</i> , 2010 , 49, 036503	1.4	12
167	Imaging mass spectrometry with nuclear microprobes for biological applications. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009 , 267, 2144-2148	1.2	12
166	Molecular dynamics study of surface modification with a glancing angle gas cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 255, 265-268	1.2	12

165	Secondary ion emission from bio-molecular thin films under ion bombardment. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 256, 489-492	1.2	12
164	Gold nanoparticles sputtered by single ions and clusters. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 851-854	1.2	12
163	Cluster species and cluster size dependence of damage formation by cluster ion impact. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 861-865	1.2	12
162	Novel shallow junction technology using decaborane (B/sub 10/H/sub 14/)		12
161	Range and Damage Distribution in Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , 1996 , 438, 363		12
160	Study of density effect of large gas cluster impact by molecular dynamics simulations. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009 , 267, 2999-3001	1.2	11
159	High-speed processing with high-energy SF6 cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 257, 666-669	1.2	11
158	MD simulation study of the sputtering process by high-energy gas cluster impact. <i>Applied Surface Science</i> , 2008 , 255, 944-947	6.7	11
157	Shallow junction formation by decaborane molecular ion implantation. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2000 , 18, 445		11
156	Investigation of damage formation by gas cluster ion bombardment. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1996 , 112, 89-93	1.2	11
155	The emission process of secondary ions from solids bombarded with large gas cluster ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009 , 267, 2601-2604	1.2	10
154	Study of crater formation and sputtering process with large gas cluster impact by molecular dynamics simulations. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009 , 267, 1424-1427	1.2	10
153	Anisotropic Etching Using Reactive Cluster Beams. <i>Applied Physics Express</i> , 2010 , 3, 126501	2.4	10
152	Molecular dynamics simulation of fluorine ion etching of silicon. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2001 , 180, 317-321	1.2	10
151	SPUTTERING WITH GAS CLUSTER-ION BEAMS. <i>Surface Review and Letters</i> , 1996 , 03, 1017-1021	1.1	10
150	Ion-induced damage evaluation with Ar cluster ion beams. <i>Surface and Interface Analysis</i> , 2013 , 45, 167-170		9
149	ITO surface smoothing with argon cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2006 , 242, 140-142	1.2	9
148	Modeling of surface smoothing process by cluster ion beam irradiation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 842-845	1.2	9

147	Molecular effect on projected range in ultralow-energy ion implantation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 211, 206-210	1.2	9
146	Development of 1 mA cluster ion beam source. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2005 , 237, 455-458	1.2	9
145	Cluster size effect on reactive sputtering by fluorine cluster impact using molecular dynamics simulation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2001 , 180, 164-170	1.2	9
144	Abnormal solid solution and activation behavior in Ga-implanted Si(100). <i>Applied Physics Letters</i> , 1987 , 51, 2037-2039	3.4	9
143	Analysis of liquid materials in low vacuum with Wet-SIMS. <i>Surface and Interface Analysis</i> , 2014 , 46, 1133-1136	1.3	8
142	Fullerene ion irradiation to silicon. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1997 , 121, 480-483	1.2	8
141	Energy distribution of high-energy cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 261, 647-650	1.2	8
140	Atomistic study of cluster collision on solid surfaces. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 206, 838-841	1.2	8
139	Polycarbonate surface modified by argon cluster ion beams. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 1999 , 17, 2653	1.3	8
138	Development of ambient SIMS using mega-electron-volt-energy ion probe. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2016 , 34, 03H111	1.3	8
137	Solvent-free silver-nanoparticle surface-assisted laser desorption/ionization imaging mass spectrometry of the Irganox 1010 coated on polystyrene. <i>International Journal of Mass Spectrometry</i> , 2016 , 404, 1-7	1.9	8
136	Prolific cluster emission in sputtering of phenylalanine by argon-cluster ion bombardment. <i>International Journal of Mass Spectrometry</i> , 2014 , 360, 54-57	1.9	7
135	Using ellipsometry for the evaluation of surface damage and sputtering yield in organic films with irradiation of argon cluster ion beams. <i>Surface and Interface Analysis</i> , 2011 , 43, 84-87	1.5	7
134	Molecular dynamics simulations of large fluorine cluster impact on silicon with supersonic velocity. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011 , 269, 1582-1585	1.2	7
133	LOW-DAMAGE SURFACE TREATMENT BY GAS CLUSTER-ION BEAMS. <i>Surface Review and Letters</i> , 1996 , 03, 891-895	1.1	7
132	Low-damage surface smoothing of laser crystallized polycrystalline silicon using gas cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 257, 658-661	1.2	7
131	Secondary ion emission from Si bombarded with large Ar cluster ions under UHV conditions. <i>Applied Surface Science</i> , 2008 , 255, 880-882	6.7	7
130	High-intensity Si cluster ion emission from a silicon target bombarded with large Ar cluster ions. <i>Applied Surface Science</i> , 2006 , 252, 6550-6553	6.7	7

129	Craters produced on Al, Cu and Au by Ar cluster impacts. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2001 , 175-177, 36-39	1.2	7
128	Ultra Shallow Junction Formation by Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , 1998 , 532, 17		7
127	Study of the Etching Reaction by Atomic Chlorine Using Molecular Beam Scattering. <i>Japanese Journal of Applied Physics</i> , 1994 , 33, 2252-2254	1.4	7
126	High-aspect-ratio patterning by ClF ₃ -Ar neutral cluster etching. <i>Microelectronic Engineering</i> , 2015 , 141, 145-149	2.5	6
125	Yields and images of secondary ions from organic materials by different primary Bi ions in time-of-flight secondary ion mass spectrometry. <i>Rapid Communications in Mass Spectrometry</i> , 2016 , 30, 476-82	2.2	6
124	Ambient analysis of liquid materials with Wet-SIMS. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2016 , 371, 189-193	1.2	6
123	Biomaterial imaging with MeV-energy heavy ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2014 , 332, 326-329	1.2	6
122	Molecular dynamics study of crater formation by core-shell structured cluster impact. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2012 , 282, 29-32	1.2	6
121	Energy effects on the sputtering yield of Si bombarded with gas cluster ion beams 2011 ,		6
120	High-speed processing with Cl ₂ cluster ion beam. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009 , 267, 1444-1446	1.2	6
119	High Speed Si Etching with ClF ₃ Cluster Injection 2011 ,		6
118	Cluster ion implantation for shallow junction formation		6
117	Low-temperature formation of perovskite PbTiO ₃ films by O ₂ cluster ion-assisted deposition. <i>Materials Chemistry and Physics</i> , 1998 , 54, 255-257	4.4	6
116	Low damage smoothing of magnetic materials using off-normal gas cluster ion beam irradiation. <i>Surface and Coatings Technology</i> , 2007 , 201, 8632-8636	4.4	6
115	Energy distributions of high current cluster ion beams. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2005 , 241, 604-608	1.2	6
114	Ammonia Cluster Beam for Group-III Nitride Synthesis. <i>Physica Status Solidi A</i> , 2000 , 180, 251-256		6
113	High-intensity oxygen cluster ion beam generation and its application to cluster ion-assisted deposition. <i>European Physical Journal D</i> , 1999 , 9, 635-638	1.3	6
112	Ionised cluster beams as a hardness measurement tool. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1999 , 148, 47-52	1.2	6

111	Molecular imaging of alkaloids in khat (<i>Catha edulis</i>) leaves with MeV-SIMS. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2017 , 404, 140-145	1.2	5
110	Reactive etching by ClF ₃ /Ar neutral cluster beam with scanning. <i>Japanese Journal of Applied Physics</i> , 2016 , 55, 06HB01	1.4	5
109	An electrostatic quadrupole doublet focusing system for MeV heavy ions in MeV-SIMS. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2013 , 315, 356-359	1.2	5
108	Depth profiling analysis of damaged arginine films with Ar cluster ion beams. <i>Surface and Interface Analysis</i> , 2012 , 44, 729-731	1.5	5
107	Surface processing with high-energy gas cluster ion beams. <i>Surface and Coatings Technology</i> , 2007 , 201, 8646-8649	4.4	5
106	Molecular dynamics study of monomer and dimer emission processes with high energy gas cluster ion impact. <i>Surface and Coatings Technology</i> , 2007 , 201, 8427-8430	4.4	5
105	Surface oxidation of Si assisted by irradiation with large gas cluster ion beam in an oxygen atmosphere. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 256, 350-353	1.2	5
104	Secondary ion measurements for oxygen cluster ion SIMS. <i>Applied Surface Science</i> , 2006 , 252, 7290-72926.7		5
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